



Future Normal in Semiconductor

2025년 2월 14일(금), 10:55-12:40

Room J(스페이스 II+III), 6층

K. Memory (Design & Process Technology) 분과

062_[FJ2-K] Oxide Channel based Memory Technology

좌장: 권민우 교수(강릉원주대학교), 이성태 교수(홍익대학교)

<p>FJ2-K-1 10:55-11:10</p>	<p>Photoprogrammable OFET Memory Devices based on IGZO Floating Gate Gyeongho Lee^{1,2}, Dong Hyun Lee³, and Hocheon Yoo^{3,4} ¹Department of Semiconductor Total Solution Center, KICET, ²Department of Materials Science and Engineering, Korea University, ³Department of Electronic Engineering, Gachon University, ⁴Department of Semiconductor Engineering, Gachon University</p>
<p>FJ2-K-2 11:10-11:25</p>	<p>Oxide Channel-Based Ferroelectric NAND Device with Enhanced Memory Window Using a Source-Tied Metal Cover Structure Hongrae Joh, Giuk Kim, Jihye Ock, Seungyeob Kim, Sangmok Lee, Sangho Lee, and Sanghun Jeon School of Electrical Engineering, KAIST</p>
<p>FJ2-K-3 11:25-11:40</p>	<p>Comparative Evaluation of the Impact of WL Off Voltage on BL Disturbance in SOI and IGZO Cell Transistors for 4F² DRAM Application Seong Hoon Jeon, Wonjung Kim, Seungki Kim, Soohong Eo, Sae Him Jung, Jong-Ho Bae, Sung-Jin Choi, Dong Myong Kim, and Dae Hwan Kim School of Electrical Engineering, Kookmin University</p>
<p>FJ2-K-4 11:40-11:55</p>	<p>Demonstration of Amorphous InGaZnOx 2T-DRAM Array and Analog Operation Capability for Processing-In-Memory Application Hyunwook Jeong¹, Junseong Park¹, Haesung Kim¹, Hyojin Yang¹, Yubin Choi¹, Hwan Jin Kim¹, Sujong Kim¹, Sung-Jin Choi¹, Dae Hwan Kim¹, Dong Myong Kim², Seongjae Cho³, and Jong-Ho Bae¹ ¹School of the Electronic Engineering, Kookmin University, ²Department of Advanced Technology, DGIST, ³Department of Electronic and Electrical Engineering, Ewha Womans University</p>
<p>FJ2-K-5 11:55-12:10</p>	<p>Comparative Optimization of Synaptic Characteristics in IGZO-Based Memristors Through Interface Engineering With Metal Electrode Jae Woo Lee, Dong Hyeop Shin, Wonjung Kim, Seung Joo Myoung, Changwook Kim, Jong-Ho Bae, Sung-Jin Choi, Dong Myong Kim, and Dae Hwan Kim School of Electrical Engineering, Kookmin University</p>



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<p>FJ2-K-6 12:10-12:25</p>	<p>Highly Linear and Symmetric Multilevel IGZO 2T Synaptic Device Utilizing Identical Potentiation and Depression Pulses Suwon Seong¹, Taejun Ha¹, Sangwook Jung², Sunwoong Ham², and Yoonyoung Chung^{1,2,3,4} ¹Department of Electrical Engineering, POSTECH, ²Graduate School of Semiconductor Technology, POSTECH, ³Department of Semiconductor Engineering, POSTECH, ⁴Center for Semiconductor Technology Convergence, POSTECH</p>
<p>FJ2-K-7 12:25-12:40</p>	<p>Disturbance-Free Parallel Programming for Multilevel IGZO 2T Synapse Taejun Ha¹, Suwon Seong¹, and Yoonyoung Chung^{1,2,3} ¹Department of Electrical Engineering, ²Department of Semiconductor Engineering, ³Center for Semiconductor Technology Convergence, POSTECH</p>